	·	(c22c021/\$.ipc. and (sc or scandium or si or silicon or ti or	USPAT;	2003/09/20 17:09
-	3		US-PGPUB;	2003/09/20 17:09
		titanium or hf or hafnium) and ((grain or size) near2 ("mu.m"		
		or "mu" or "mu." or micron or micrometer or ".mu.m" or	EPO; JPO;	
		".mu." or "mum" or mu.m or \$1"mu.m")) and ((sputter\$4 or	DERWENT	
		physical or vapor) near3 target)) not ((c22c021/\$.ipc. and (sc		
		or scandium or si or silicon or ti or titanium or hf or hafnium)		
		and (ecae or ((equal or channel) near2 (extrusion or extruded		
		or extrude))) and ((grain or size) near2 ("mu.m" or "mu" or		
		"mu." or micron or micrometer or ".mu.m" or ".mu." or "mum"		
		or mu.m or \$1"mu.m")) and ((sputter\$4 or physical or vapor)		
		near3 target)) ((148/437,415.ccls. or 420/548,552.ccls.) and		
		rears target)) ((146/457,415.ccis. 01420/546,552.ccis.) and		
		(sc or scandium or si or silicon or ti or titanium or hf or		
		hafnium) and (grain or size near2 ("mu.m" or "mu" or "mu." or		
		micron or micrometer or ".mu.m" or ".mu." or "mum" or mu.m		
		or \$1"mu.m")) and ((sputter\$4 or physical or vapor) near3		
		target)))		
_	12		USPAT;	2003/09/20 18:44
		titanium or hf or hafnium) and ((grain or size) near2 ("mu.m"	US-PGPUB;	
		or "mu" or "mu." or micron or micrometer or ".mu.m" or	EPO; JPO;	}
		".mu." or "mum" or mu.m or \$1"mu.m")) and ((sputter\$4 or	DERWENT	
			DEIXVEN	
	_	physical or vapor) near3 target)	LICDAT	2002/00/00 47:46
-	2	5780755.pn.	USPAT;	2003/09/20 17:16
		'	US-PGPUB;	1
			EPO; JPO;	
			DERWENT	
-	2	(sputter\$4 near2 target) and morillo.xa.	USPAT;	2003/09/20 17:16
	_	(US-PGPUB:	
			EPO; JPO;	
			DERWENT	
		=22=004/\$ in a and (a) as silican) and ((asain as size) near?	USPAT;	2003/09/20 18:44
•	9	c22c021/\$.ipc. and (si or silicon) and ((grain or size) near2		2003/09/20 10.44
		("mu.m" or "mu" or "mu." or micron or micrometer or ".mu.m"	US-PGPUB;	
		or ".mu." or "mum" or mu.m or \$1"mu.m")) and ((sputter\$4 or	EPO; JPO;	i
		physical or vapor) near3 target)	DERWENT	
_	22	(148/437,415.ccls. or 420/548,552.ccls.) and (si or silicon)	USPAT;	2003/09/20 18:45
		and (grain or size near2 ("mu.m" or "mu" or "mu." or micron	US-PGPUB;	
		or micrometer or ".mu.m" or ".mu." or "mum" or mu.m or	EPO; JPO;	
		\$1"mu.m")) and ((sputter\$4 or physical or vapor) near3	DERWENT	
		target)		
	20		USPAT:	2003/09/20 18:46
-	30	((al or aluminum) near2 (alloy or base or based or balance))	,	2000/09/20 10:40
		and (si or silicon) and ((grain or size) near2 ("mu.m" or "mu"	US-PGPUB;	
		or "mu." or micron or micrometer or ".mu.m" or ".mu." or	EPO; JPO;	
		"mum" or mu.m or \$1"mu.m")) and ((sputter\$4 or physical or	DERWENT	
		vapor) near3 target) and (148/\$.ccls. or 420/\$.ccls.)		
-	46	(c22c021/\$.ipc. and (si or silicon) and ((grain or size) near2	USPAT;	2003/09/20 18:46
	ļ	("mu.m" or "mu" or "mu." or micron or micrometer or ".mu.m"	US-PGPUB;	
		or ".mu." or "mum" or mu.m or \$1"mu.m")) and ((sputter\$4 or	EPO; JPO;	
]	physical or vapor) near3 target)) ((148/437,415.ccls. or	DERWENT	
			DEIXVENI	
		420/548,552.ccls.) and (si or silicon) and (grain or size near2	•	
		("mu,m" or "mu" or "mu." or micron or micrometer or ".mu.m"		
		or ".mu." or "mum" or mu.m or \$1"mu.m")) and ((sputter\$4 or		
		physical or vapor) near3 target)) (((al or aluminum) near2		
		(alloy or base or based or balance)) and (si or silicon) and		
		((grain or size) near2 ("mu.m" or "mu" or "mu." or micron or		
		micrometer or ".mu.m" or ".mu." or "mum" or mu.m or		
		\$1"mu.m")) and ((sputter\$4 or physical or vapor) near3		
	[target) and (148/\$.ccls. or 420/\$.ccls.))	,	
			USPAT;	2003/09/20 18:54
-	15	(148/437,415.ccls. or 420/548,552.ccls.) and (sc or scandium		2003/03/20 10,04
		or si or silicon or ti or titanium or hf or hafnium) and	US-PGPUB;	
		((sputter\$4 or physical or vapor) near3 target) and (high	EPO; JPO;	
	L	near2 purity)	DERWENT	